

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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| Serial No. 09/546,174 | Confirmation No.: 4793 |
| Application of: Chih-Chien Liu, Ta-Shan Tseng, W. B. Shieh, J. Y. Wu, Water Lur and Shih-Wei Sun | Art Unit: 1711 |
| Filed: April 11, 2000 | Examiner: Sergeant, Rabon A. |
| Attorney Docket No. UMC-96-279 CON | Customer No.: 25235 |
| For: HIGH DENSITY PLASMA CHEMICAL VAPOR DEPOSITION PROCESS | |

RESPONSE TO OFFICE ACTION DATED SEPTEMBER 8, 2006

MAIL STOP RCE
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

This response is filed with a request for continued examination and a petition for two month extension of the period for response the office communication mailed September 8, 2006. Please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims beginning on page 2 of this paper.

Remarks begin on page 11 of this paper.